

[METHOD FOR DETECTING DEFECT OF SEMICONDUCTOR DEVICE]

Abstract

A method for detecting defects of a semiconductor device is provided. The semiconductor device comprises at least a substrate, a gate, a source region, a drain region, a plug, an insulating layer, and a conducting line. The plug electrically connects the source region or the drain region and is above a portion of the gate. At least a defect exists between the plug and the gate. The method comprises: polishing the semiconductor device until the plug above the gate is removed; cleaning the semiconductor device; removing the insulating layer between the gate and the plug; and detecting the defect between the plug and the gate.